SPICE Model for MOSFETs in sedra_lib.lib (1/2)

SPICE Parameter	Book Symbol	Description	Units
		Basic Model Parameters	
LEVEL		MOSFET model selector	
TOX	t_{ox}	Gate-oxide thickness	m
COX	C_{ox}	Gate-oxide capacitance, per unit area	F/m ²
UO	μ	Carrier mobility	cm ² /V·s
KP	k'	Process transconductance parameter	A/V ²
LAMBDA	λ	Channel-length modulation coefficient	V^{-1}
		Threshold Voltage Parameters	
VTO	V_{t0}	Zero-bias threshold voltage	V
GAMMA	γ	Body-effect parameter	$V^{1/2}$
NSUB	N_A, N_D	Substrate doping	cm^{-3}
PHI	$2\phi_f$	Surface inversion potential	V
		MOSFET Diode Parameters	
JS		Body-junction saturation-current density	A/m^2
CJ		Zero-bias body-junction capacitance, per unit area over the drain/source region	F/m ²
MJ		Grading coefficient, for area component	
CJSW		Zero-bias body-junction capacitance, per unit length along F/m the sidewall (periphery) of the drain/source region	
MJSW		Grading coefficient, for sidewall component	
PB	V_0	Body-junction built-in potential	V
		MOSFET Dimension Parameters	
LD	L_{ov}	Lateral diffusion into the channel	m
		from the source/drain diffusion regions	
WD		Sideways diffusion into the channel	m
		from the body along the width	
		MOS Gate-Capacitance Parameters	
CGBO		Gate-body overlap capacitance, per unit channel length	F/m
CGDO	C_{ov}/W	Gate-drain overlap capacitance, per unit channel width	F/m
CGSO	C_{ov}/W	Gate-source overlap capacitance, per unit channel width	F/m

Reference: Adel S. Sedra and Kenneth C. Smith, Microelectronic Circuit 7th ed. New York, Oxford Univ. Press, 2016 app. B.1.4, ppB-7

SPICE Model for MOSFETs in sedra_lib.lib (2/2)

Technology	$L_{ m min}$	$W_{ m min}$	$\left(V_{DD} + \left V_{SS}\right \right)_{\max}$
5-µm CMOS	5μm	12.5 μm	10 V
0.5-μm CMOS	0.5 μm	1.25 μm	3.3 V
0.18-μm CMOS	0.18 μm	0.22 μm	1.8 V

L_{min}: minimum channel length W_{min}: minimum channel width (VDD+|VSS|)_{max}: maximum supply voltage

Table B.3 Values of the Level-1 MOSFET Model Parameters for Two CMOS Technologies¹

						<u> </u>	
	5-μm CMOS Process		0.5-μm CM	0.5-μm CMOS Process		0.18-μm CMOS Process	
	NMOS	PMOS	NMOS	PMOS	NMOS	PMOS	
LEVEL	1	1	1	1	1	1	
TOX	8.50e-08	8.50e-08	9.50e-09	9.50e-09	4.08e-09	4.08e-09	
UO	750	250	460 680	115 200	291	102	
LAMBDA	0.01	0.03	0.1	0.2	0.08	0.11	
GAMMA	1.4	0.65	0.5	0.45	0.3	0.3	
VTO	1	-1	0.7	-0.8	0.5	-0.45	
PHI	0.7	0.65	0.8	0.75	0.84	0.8	
LD	7.00e-07	6.00e-07	8.00e-08	9.00e-08	10e-9	10e.9	
JS	1.00e-06	1.00e-06	1.00e-08	5.00e-09	8.38e-6	4.00e-07	
CJ	4.00e-04	1.80e-04	5.70e-04	9.30e-04	1.60e-03	1.00e-03	
MJ	0.5	0.5	0.5	0.5	0.5	0.45	
CJSW	8.00e-10	6.00e-10	1.20e-10	1.70e-10	2.04e-10	2.04e-10	
MJSW	0.5	0.5	0.4	0.35	0.2	0.29	
PB	0.7	0.7	0.9	0.9	0.9	0.9	
CGBO	2.00e-10	2.00e-10	3.80e-10	3.80e-10	3.80e-10	3.50e-10	
CGDO	4.00e-10	4.00e-10	4.00e-10	3.50e-10	3.67e-10	3.43e-10	
CGSO	4.00e-10	4.00e-10	4.00e-10	3.50e-10	3.67e-10	3.43e-10	

¹In PSpice, we have created MOSFET parts corresponding to the above models. Readers can find these parts in the SEDRA.olb library, which is available online at www.oup.com/us/sedrasmith. The NMOS and PMOS parts for the 0.5-μm CMOS technology are labeled NMOS0P5_BODY and PMOS0P5_BODY, respectively. The NMOS and PMOS parts for the 5-μm CMOS technology are labeled NMOS5P0_BODY and PMOS5P0_BODY, respectively. Furthermore, parts NMOS5P0 and PMOS5P0 are created to correspond to, respectively, part NMOS0P5_BODY with its body connected to net 0 and part PMOS0P5_BODY with its body connected to net VDD.

Vacuum permittivity:

$$\varepsilon_0 = 8.854 \times 10^{-12} (\text{F} \cdot \text{m}^{-1})$$

Oxide permittivity:

$$\varepsilon_{\rm ox} = 3.9\varepsilon_0$$